Photocontrol of the adsorption behavior of phenol for azobenzenemontmorillonite intercalation compound

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Electronic Supplementary Information

Contents

1. The reversible change in the XRD pattern of the AZ⁺-montmorillonite-phenol upon UV and visible light irradiation (Figure S1).

 The change in the XRD pattern of the AZ⁺-montmorillonite-phenol with UV irradiated time to 30 min (Figure S2).

Figure S1



Figure S1. The reversible change in the XRD pattern of the AZ⁺-montmorillonite-phenol (mass ratio of 4:1 (added phenol : AZ⁺-montmorillonite) upon UV and visible light irradiation. (a) Before irradiation,
(b) UV irradiated (30 min), (c) vis. irradiated (30 min), (d) after 2nd UV irradiation and
(e) after 2 nd vis. irradiation.



Figure S2. The change in the XRD pattern of the AZ^+ -montmorillonite-phenol upon UV irradiation. (a) Before irradiation, (b) UV irradiated for 5 min, (c) 10 min, (d) 20 min and (e) 30 min (mass ratio of 4:1 (added phenol : AZ^+ -montmorillonite)).